

# Critical Coupling in Polaritonic Metasurfaces

Peter Chang Nishant Nookala Dr. Mikhail Belkin



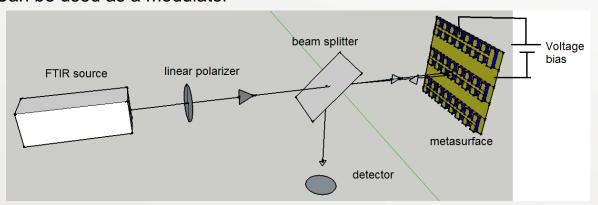






#### **Problem and Context**

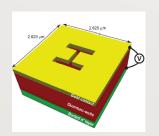
- Metasurfaces are flat, thin optical components that can introduce abrupt changes to the properties of incident light.
- Goal: Change the reflection of a mid-infrared beam with a voltage bias.
- Can be used as a modulator

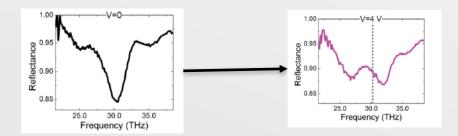


- Critical coupling and no reflection when there is no voltage bias across the metasurface.
- Increase reflection with a voltage bias.

# Previous work:

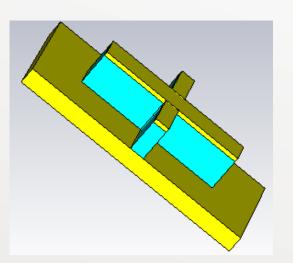
- A metasurface made with a pattern of H shaped openings.
- See a reflection change going from 0V to 4V

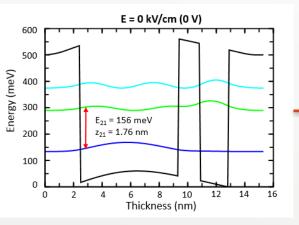


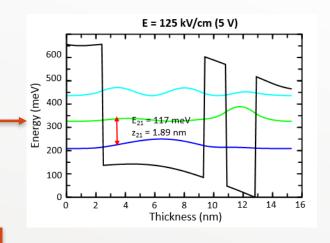




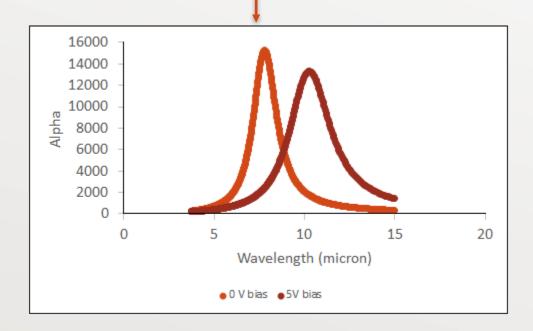
#### Theory





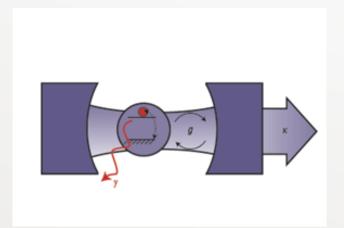


- The gold dipole acts as an optical cavity which, at the resonance frequency, confines light inside a subwavelength volume.
- The MQW acts as a two level system, whose absorption can be tuned by a voltage bias.

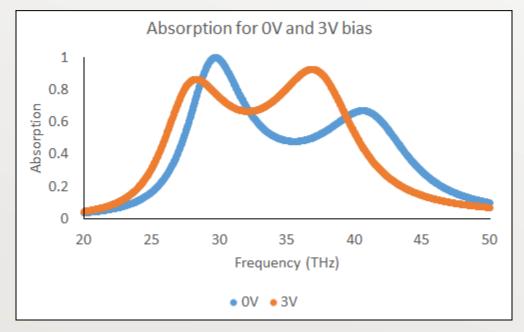




#### Theory continued



- Coupling an optical cavity to an IST forms a polariton
- A polariton exhibits two energies, which is observed in a dampening and splitting of the absorption spectrum.



Khitrova, G., Gibbs, H. M., Kira, M., Koch, S. W., & Scherer, A. (2006). Vacuum Rabi splitting in semiconductors. *Nature Physics*, *2*(2), 81–90.

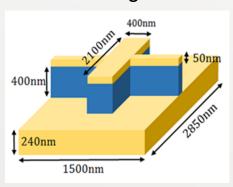


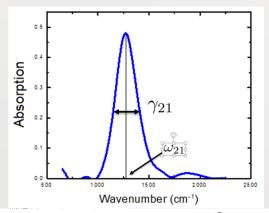
#### **Design and Simulation**

The unit cell is constructed in CST simulation software.

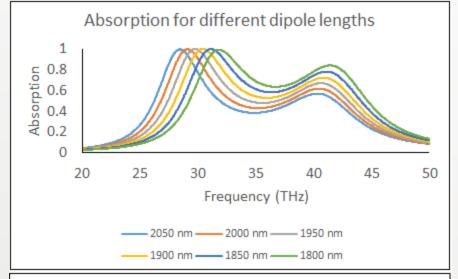
 Electric permittivity values are calculated and the optical response is observed for different dipole lengths to look for largest absorption change

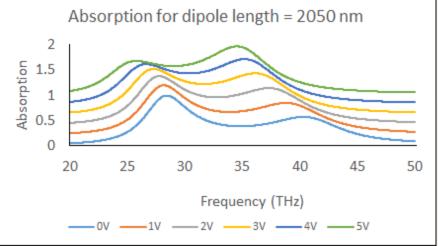
under a voltage bias





$$\epsilon_{\perp}(\omega) \approx \epsilon_{core}(\omega) + \frac{N_{e}(ez_{12}^{2})}{\epsilon_{0}\hbar((\omega_{21} - \omega) - i\gamma_{21})}$$

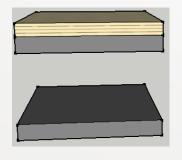




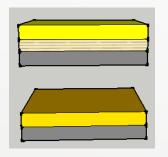


#### **Fabrication**

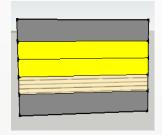
Starting set up



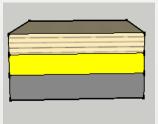
Deposit AU 120 nm



Wafer bond



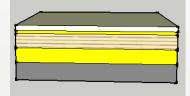
Polish and wet etch



Deposit Au 50 nm



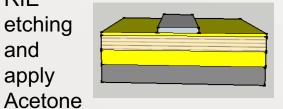
Deposit SiN 200 nm



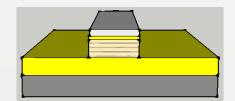
E-beam litho



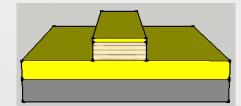
RIE etching and apply



**ICP** etching

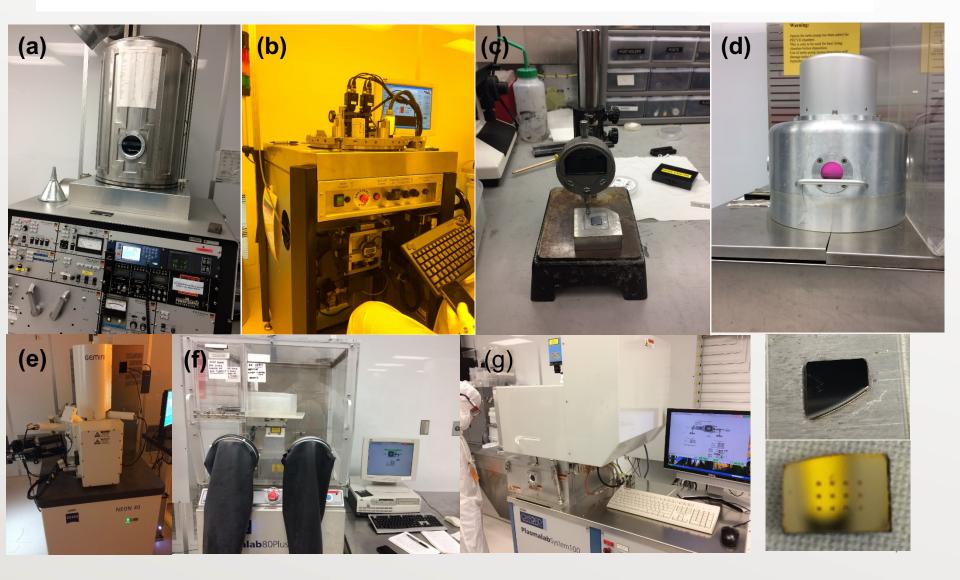


**Apply** HF





(a) e-beam evaporator metal deposition  $\rightarrow$  (b) wafer bond  $\rightarrow$  (c) polish and wet etch  $\rightarrow$  (d) PECVD SiN deposition  $\rightarrow$  (e) EBL  $\rightarrow$  (f-g) RIE and ICP plasma etch



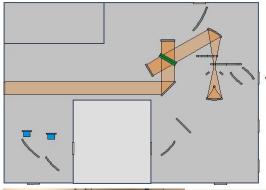


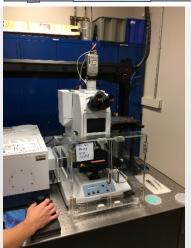
### **Absorption Measurements**

- FTIR Fourier Transform Infrared Spectroscopy
- A broadband source is sent into an interferometer.
- Reflection results are converted from reflection per mirror position to reflection per frequency.

 FTIR signal is outsourced into an infrared microscope objective.

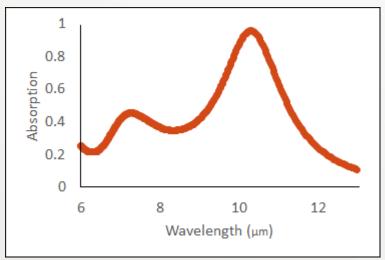






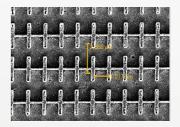


### **Critical Coupling**

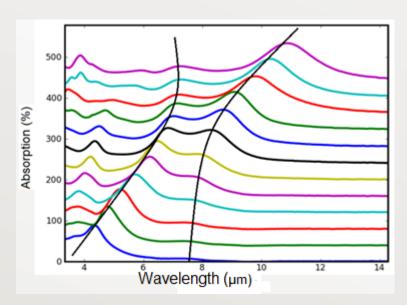


Experimental results for a dipole length of 2300 nm. Absorption peak of 96% at ~ 10.3 µm.

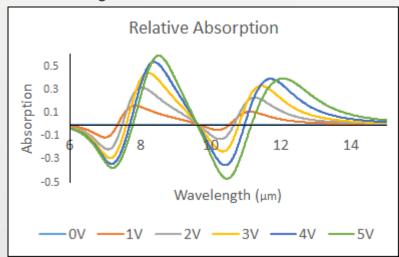
- A total of 12 patterns with dipole lengths ranging from 1300- 2400 nm were made.
- Critical Coupling was achieved with up to 97% absorption.



Simulation Results for applying different DC bias voltages.



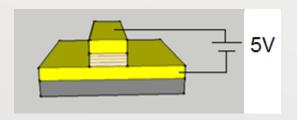
Experimental results for dipoles with mask lengths 1300 – 2400 nm. Results are offset by 40% for clarity.





# **Future Work and Applications**

- We plan to apply a voltage bias to contacts on the gold surface and ground plane to demonstrate an electrically tunable metasurface operating in the midinfrared spectral range.
- Stark Tunable metasurfaces have already been demonstrated before. For this project, we hope to achieve a larger absorption change in designing for critical coupling in the unbiased case.
- Potential applications include an electrically tunable optical filter or laser modulator.





# Acknowledgements

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